

**IN THE CLAIMS:**

Claims 1-41 were filed with the present CIP application.

Claims 1-8, 21-24, 28, 30-38, 40 and 41 were withdrawn from consideration.

Claims 9-20, 25-27, 29 and 39 are now pending.

Claims 9-13, 15, 16, 18-20, 25-27, 29 and 39 have been rejected. Claims 14 and 17 were objected to.

Please cancel claims 11, 25-27, 29 and 39.

Please amend claims 10 and 17-19, as follows:

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1. (Withdrawn)
  2. (Withdrawn)
  3. (Withdrawn)
  4. (Withdrawn)
  5. (Withdrawn)
  6. (Withdrawn)
  7. (Withdrawn)
  8. (Withdrawn)
  9. (Cancelled) An apparatus for containing a substrate, comprising:  
a plurality of components including at least one vacuum chamber, the components defining an peripheral envelope of space; and

at least one pump having an inlet connected to the vacuum chamber and an outlet exhausting gas to atmospheric pressure, whereby the pump is locatable within the peripheral envelope of space defined by the components.

10. (Currently Amended) An apparatus for processing a substrate, comprising:  
a plurality of vacuum chambers defining an envelope of space in a clean room;  
and

at least two pumps, each pump having an inlet connected to at least one of the chambers for evacuating gas in the chamber and an outlet that exhausts the evacuated gas to a pressure approximately equal to atmospheric pressure, the pumps being located within the envelope of space defined by the chambers;

(12) and wherein each of the plurality of vacuum chambers includes:

at least one load-lock chamber; and

at least two transfer chambers, with each transfer chamber having a plurality of process chambers disposed in a radial fashion there around.

11. (Cancelled) The apparatus of claim 10, wherein the plurality of vacuum chambers includes:

at least one process chamber;  
at least one load-lock chamber; and  
at least one transfer chamber.

12. (Currently Amended) The apparatus of claim 11 10, wherein at least one of the process chambers and the load-lock chamber are elevated off of the clean room floor.

13. (Original) The apparatus of claim 12, wherein each of the pumps is disposed beneath one of the elevated process chambers and a fourth pump is disposed beneath one of the elevated load-lock chambers.

14. (Currently Amended) The apparatus of claim 12, wherein a ~~first transfer chamber is disposed adjacent a second transfer chamber, the first and second transfer~~

~~chambers having a plurality of process chambers disposed in a radial fashion there around and wherein two of the pumps are each disposed between adjacent process chambers,~~ one pump is disposed beneath a load-lock chamber, and two pumps are disposed each beneath one of the process chambers.

15. (Original) The apparatus of claim 12, further comprising at least four process chambers and two load-lock chambers connected to the transfer chamber and at least one pump disposed beneath each of the process chambers and at least one pump disposed beneath one of the load-lock chambers.

16. (Original) The apparatus of claim 15, further comprising two pumps stacked vertically and disposed at least partially beneath one of the load-lock chambers.

17. (Currently Amended) The apparatus of claim 11 10, further comprising a  
wherein each transfer chamber with has at least four process chambers and two  
load-lock chambers disposed therearound; and  
wherein the apparatus further comprises six pumps disposed at a first end of the  
envelope beneath a gas supply panel, the pumps substantially within the footprint of the  
apparatus.

18. (Currently Amended) The apparatus of claim 11 10, wherein the pumps are each housed in an enclosure, the enclosure including noise and vibration reducing members.

19. (Currently Amended) The apparatus of claim 11 10, wherein the pumps include movable members to facilitate moving the pumps around a surface of a clean room floor.

20. (Original) The apparatus of claim 12, wherein two of the pumps are stacked vertically and are at least partially disposed under one of the chambers.

21. (Withdrawn)

22. (Withdrawn)
23. (Withdrawn)
24. (Withdrawn)
25. (Cancelled) An apparatus for processing a substrate, comprising:  
a transfer chamber;  
a plurality of process chambers connected to the transfer chamber; and  
a plurality of pumps disposed adjacent the transfer chamber in an alternating relationship with the process chambers within a perimeter of the apparatus as defined by the outermost edges of the chambers.
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26. (Cancelled) The apparatus of claim 25, wherein at least one of the pumps is mounted on another pump.
27. (Cancelled) A pump for use with a substrate processing apparatus, comprising:  
an inlet connected to a vacuum chamber and an outlet exhausting gas to atmospheric pressure; and  
the pump constructed and arranged to operate within an envelope of the apparatus.
28. (Withdrawn)
29. (Cancelled) The pump of claim 27, further including a vacuum chamber disposed above the pump whereby the pump and chamber are housed together in a frame, the pump within the envelope of space defined by the outer perimeter of the vacuum chamber.
30. (Withdrawn)

31. (Withdrawn)

32. (Withdrawn)

33. (Withdrawn)

34. (Withdrawn)

35. (Withdrawn)

36. (Withdrawn)

A  
37. (Withdrawn)

C  
38. (Withdrawn)

39. (Cancelled) The pump of claim 27, wherein the pump is a multiple inlet pump  
operating at least two chambers